

Title (en)

A photosensitive resin composition for use in forming a relief structure.

Title (de)

Lichtempfindliche Harzzusammensetzung zur Verwendung bei der Herstellung einer Reliefstruktur.

Title (fr)

Composition résineuse photosensible à utiliser pour la formation d'une structure en relief.

Publication

EP 0427950 A2 19910522 (EN)

Application

EP 90119036 A 19901004

Priority

JP 29611389 A 19891116

Abstract (en)

A photosensitive resin composition for use in forming a relief structure, which comprises, in specific proportions, a liquid photosensitive resin component comprising a urethane prepolymer and an addition-polymerizable ethylenically unsaturated monomer; a photopolymerization initiator; a thermal polymerization inhibitor; and a specific unsaturated amine compound. The photosensitive resin composition exhibits excellent performances such that it does not suffer from the tunnel phenomenon which is frequently observed in relief formation with respect to conventional photosensitive resin compositions, so that a photoresin relief structure made therefrom not only is characterized with a tunnel-free structure and excellent mechanical properties, but also exhibits excellent performances.

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